

ABSTRACT OF THE DISCLOSURE
EXPOSURE APPARATUS AND ARTICLE MANUFACTURING METHOD

An exposure apparatus that projects a pattern of an original onto a substrate via a projection optical system and exposes the substrate is provided. The apparatus comprises an aberration correction member arranged on an optical path of exposure light between the original and the substrate, and a driver which drives the aberration correction member. The aberration correction member includes a first optical element including a first surface having a three-fold rotational symmetric aspherical shape with respect to an optical axis of the exposure light, and a second optical element spaced apart from the first optical element along the optical axis and including a second surface facing the first surface and having an aspherical shape that complementarily corrects an aberration generated by the first optical element. The driver performs at least one of rotation about the optical axis and driving along the optical axis of at least one of the first optical element and the second optical element.

(Fig. 1)